



Docket No.: 1752-0165P  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re Patent Application of:  
Toshitsura CHO et al.

Application No.: 10/779,680

Confirmation No.: 008556

Filed: February 18, 2004

Art Unit: 1755

For: ABRASIVE SLURRY HAVING HIGH  
DISPERSION STABILITY AND  
MANUFACTURING METHOD FOR A  
SUBSTRATE

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Examiner: M. A. Marcheschi

**AMENDMENT IN RESPONSE TO FINAL OFFICE ACTION**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated December 8, 2005, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 4 of this paper.